

ABSTRACT

5           A reflective photomask blank including a substrate, a multilayer reflection film, a  
protection film and a light absorbing film that has a phase shift function is provided. The  
light absorbing film contains ruthenium and chromium and is free of oxygen and nitrogen,  
and has a ruthenium content of 64 to 74 at%, a chromium content of 26 to 36 at%, a  
thickness of 40 to 44 nm, and a reflectance of 12 to 15% and a phase shift of 200 to 230  
10 degrees with respect to exposure light being light in extreme ultraviolet range.

[Figure 1]